



IEUVI Mask TWG October 16, 2011

Preliminary Agenda

8:00 AM – 8:10 AM	Introduction / Housekeeping	David Chan, SEMATECH
8:10 AM – 8:25 AM	Report-out of IEUVI Mask TWG at BACUS	David Chan, SEMATECH
8:25 AM – 8:50 AM	E152 Standard Update	Long He, SEMATECH/Intel
8:50 AM – 9:15 AM	Gudeng EUV Carrier Development and Evaluation Update	Chenwei Ku, Gudeng
9:15 AM – 9:40 AM	Entegris EUV Carrier Status and Roadmap	Tom Kielbaso, Entegris
9:40 AM – 9:55 AM	Nikon/Canon Perspectives of Potential Improvement of Pod Performance	Kazuya Ota, Nikon
9:55 AM – 10:05 AM	Break	
10:05 AM – 10:30 AM	Automation Challenges of EUV Reticle Carriers	Suresh Biligiri, Rorze Automations
10:30 AM – 10:45 AM	Initial Learning of In-Fab Handling	Rik Jonckheere, IMEC
10:45 AM – 11:00 AM	Issues of Reticle Coatings	Kazuya Ota, Nikon
11:00 AM – 12:00 PM	Topic discussions & action plans: <ul style="list-style-type: none">- Shipping options / strategy- Reticle storage- Non-exposure tool implementation (Blank Dep, Inspection, AMIS, Clean)- Pod clean	All (Long He)



12:00 PM – 1:00 PM	Lunch	
1:00 PM – 1:10 PM	IMEC Inputs on Blank Defectivity	Rik Jonckheere, IMEC
1:10 PM – 1:25 PM	Program and Native Defect Printability	Harry Kwon, SEMATECH/Samsung
1:25 PM – 1:55 PM	EUV Mask Cleaning Challenges for 11 nm and 16 nm HP Nodes	Abbas Rastegar, SEMATECH
1:55 PM – 2:10 PM	Critical Issues for Deposition Tool	Vibhu Jindal, SEMATECH
2:10 PM – 2:25 PM	Next Generation Sources for Ion Beam Deposition Tool	Veeco
2:25 PM – 2:40 PM	Dual Pod Handler	B. A. vander Zwan, TNO
2:40 PM – 2:55 PM	Front-End Handling Strategy for Defect-Free EUV Mask Blank Deposition	Jaewoong Sohn, SEMATECH
2:55 PM – 3:10 PM	Modeling Particle Transport in Low Pressure Under Plasma Conditions	Alex Likhanskii, Tech-X
3:10 PM – 3:25 PM	Detection of Small Size Particles in Low Pressure and Component Evaluation	Gregory Denbeaux, CNSE
3:25 PM – 3:35 PM	Break	
3:35 PM – 3:50 PM	Particle Defects Originating from Valves and Possible Solutions	VAT
3:50 PM – 4:05 PM	Particle Defects Originating from Seals and Possible Solutions	Jeff Blouse, ASNA
4:05 PM – 4:20 PM	Component and Shield Cleaning Processes for Low Defectivity	David Laube, Pentagon
4:20 PM – 4:35 PM	Current Challenges of EUV Substrate and Mask Blank Cleaning	Arun Kadaksham, SEMATECH
4:35 PM – 5:00 PM	Action Plans / Meeting Adjourn	Vibhu Jindal, SEMATECH